ABSTRACT

A method of transferring a conductor pattern to a film carrier on which an electronic device is mounted. Using a mask having a conductor pattern and two or more conductor pattern positioning marks, the mask pattern is preliminarily transferred to a film carrier coated with photoresist. Deviations between the position of the transferred positioning marks with respect to reference coordinates of the film carrier and a designed position are measured, the position of the mask with respect to the film carrier is adjusted, and then the mask pattern is fully transferred to the film carrier.

Also, a mask for performing the above-described method that has a conductor pattern and two or more conductor pattern positioning marks is disclosed. Furthermore, a film carrier in which a conductor pattern and two or more conductor pattern positioning marks for the film are transferred to the surface of the conductor layer is disclosed.